



Attorney Docket No. Patent 81329A

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of: JOSEPH J. DANKO

Serial No: 09/579,593

Group Art Unit: 2877

Filed: May 26, 2000

Examiner: G. J. Stock, Jr.

For: METHOD AND APPARATUS FOR INSPECTING A PATTERNED SEMICONDUCTOR WAFER

Box Fee Amendment
Commissioner for Patents
Washington, D. C. 20231

Dear Sir:

AMENDMENT

This communication is in response to an Office Action received on this application dated July 31, 2002. It is respectfully requested that the above-identified application be amended as follows:

IN THE SPECIFICATION:

Rewrite the paragraph on page 19, lines 18-19 to read as follows:

a1 First beam of light 40-1 strikes surface 12 on semiconductor wafer 13 so as to illuminate a first striped shaped region 40-2, as can be seen in Fig. 6.

IN THE ABSTRACT:

Rewrite the Abstract to read as follows:

a2 A method and apparatus for inspecting a surface of a semiconductor wafer having repetitive patterns for contaminant particles using scattered light which involves directing two beams of light at different approach angles onto the surface in a manner

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